# PATENT COOPERATION TREATM

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#### **NOTIFICATION OF ELECTION**

(PCT Rule 61.2)

To:

Assistant Commissioner for Patents United States Patent and Trademark Office Box PCT Washington, D.C.20231 ETATS-UNIS D'AMERIQUE

Date of mailing (day/month/year) 25 August 2000 (25.08.00)

in its capacity as elected Office

International application No. PCT/GB00/00402 Applicant's or agent's file reference 4576F/JAK

International filing date (day/month/year) 10 February 2000 (10.02.00) Priority date (day/month/year)
12 February 1999 (12.02.99)

#### **Applicant**

SIDDLE, John, Robert

1.	The designated Office is hereby notified of its election made:
	X in the demand filed with the International Preliminary Examining Authority on:
İ	10 July 2000 (10.07.00)
	in a notice effecting later election filed with the International Bureau on:
2.	The election X was
	was not
	made before the expiration of 19 months from the priority date or, where Rule 32 applies, within the time limit under Rule 32.2(b).

The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland Authorized officer

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## WORLD INTELLECTUAL PROPERTY ORGANIZATION International Bureau



	Intern	tional Bureau
INTERNATIONAL APPLICATION PUBLISH	IED U	JNDER THE PATENT COOPERATION TREATY (PCT)
(51) International Patent Classification 7:		(11) International Publication Number: WO 00/47530
C03C 17/36, 17/09, C23C 14/54	A1	(43) International Publication Date: 17 August 2000 (17.08.00)
(21) International Application Number: PCT/GB0 (22) International Filing Date: 10 February 2000 (19)		BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, EE,
(30) Priority Data: 9903056.1 12 February 1999 (12.02.99)	C	SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT,
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(74) Agents: HALLIWELL, Anthony, Charles et al.; Group tual Property Dept., Pilkington European Technical Pilkington plc, Hall Lane, Lathom, Ormskirk, La L40 5UF (GB).	l Cent	re l
•		t .
(54) Title: IMPROVEMENTS IN COATING GLASS		
(57) Abstract		
A process for the production of a costed substitute	nenfar	ably glass, comprising denositing a reflective metal especially a silver

A process for the production of a coated substrate, preferably glass, comprising depositing a reflective metal, especially a silver, layer by a low pressure deposition process performed in a coating atmosphere that contains a gaseous oxygen scavenger. The presence of the gaseous oxygen scavenger alleviates oxidation of the silver layer by any oxygen gas present in the coating atmosphere. The gaseous oxygen scavenger may be a hydrocarbon and is preferably methane. The coating process is preferably sputtering.

# PATENT COOPERATION TREATY

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## INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Article 36 and Rule 70)

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		nt's file reference	FOR FURTHER AC	TION		cation of Transmittal of International	
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Internationa	al applic	cation No.	International filing date (d	day/month	/year)	Priority date (day/month/year)	
PCT/GB00/00402 10/02/2000						12/02/1999	
C03C17/3		nt Classification (IPC) or na	tional classification and IPC				
Applicant PILKING	TON	PLC et al.					
		tional preliminary exam mitted to the applicant a		prepared	by this Int	ernational Preliminary Examining Authority	
2. This F	REPO	RT consists of a total of	5 sheets, including this	cover st	neet.		
be (s	een ar see Ru	mended and are the bas	sis for this report and/or of the Administrative	sheets c	ontaining re	on, claims and/or drawings which have ectifications made before this Authority he PCT).	
3. This re	_	contains indications rela	ting to the following iten	ns:			
11		Priority					
111		Non-establishment of o	pinion with regard to no	velty, inv	entive step	and industrial applicability	
IV		Lack of unity of invention	on				
V			nder Article 35(2) with re ons suporting such state		novelty, inv	entive step or industrial applicability;	
VI		Certain documents cite	· -				
VII		Certain defects in the ir	nternational application	-	•		
VIII		Certain observations or	n the international applic	ation			
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Tel. +31 70 340 - 2040 Tx: 31 651 epo nl Fax: +31 70 340 - 3016  Telephone No. +31 70 340 2747							

# INTERNATIONAL PRELIMINARY EXAMINATION REPORT

International application No. PCT/GB00/00402

I.	Bas	sis of the report	
1.	the and	receiving Office in re	ents of the international application (Replacement sheets which have been furnished to sponse to an invitation under Article 14 are referred to in this report as "originally filed" this report since they do not contain amendments (Rules 70.16 and 70.17)):
	1-7	a	s originally filed
	Cla	ims, No.:	
	1-2	3 a	s originally filed
2.		•	age, all the elements marked above were available or furnished to this Authority in the ternational application was filed, unless otherwise indicated under this item.
	The	ese elements were av	ailable or furnished to this Authority in the following language: , which is:
		the language of a tra	anslation furnished for the purposes of the international search (under Rule 23.1(b)).
		the language of pub	lication of the international application (under Rule 48.3(b)).
		the language of a tra 55.2 and/or 55.3).	anslation furnished for the purposes of international preliminary examination (under Rule
3.		-	eotide and/or amino acid sequence disclosed in the international application, the examination was carried out on the basis of the sequence listing:
		contained in the inte	rnational application in written form.
		filed together with th	e international application in computer readable form.
		furnished subsequer	ntly to this Authority in written form.
		furnished subseque	ntly to this Authority in computer readable form.
			he subsequently furnished written sequence listing does not go beyond the disclosure in dication as filed has been furnished.
		The statement that the listing has been furn	he information recorded in computer readable form is identical to the written sequence ished.
1.	The	amendments have r	esulted in the cancellation of:
		the description,	pages:
		the claims,	Nos.:
		the drawings,	sheets:

5. 

This report has been established as if (some of) the amendments had not been made, since they have been considered to go beyond the disclosure as filed (Rule 70.2(c)):



International application No. PCT/GB00/00402

(Any replacement sheet containing such amendments must be referred to under item 1 and annexed to this report.)

- 6. Additional observations, if necessary:
- V. Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement
- 1. Statement

Novelty (N)

Yes: No:

Claims 1-20 Claims 21-23

Inventive step (IS)

Yes:

Claims 1-20

No:

Claims 21-23

Industrial applicability (IA)

Yes:

Claims 1-23

No: Claims

- 2. Citations and explanations see separate sheet
- VI. Certain documents cited
- 1. Certain published documents (Rule 70.10)

and / or

2. Non-written disclosures (Rule 70.9)

see separate sheet

## **EXAMINATION REPORT - SEPARATE SHEET**

### Re Item V

Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

### 1. Subject-matter

Claims 1 - 20 of the application define a low pressure deposition process for coating a substrate with a reflective metal layer performed in a coating atmosphere that contains an oxygen scavenger. Independent process claim further defines that hydrogen as an oxygen scavenger is excluded when a multilayer is deposited comprising a bismuth oxide layer. Independent process claim 19 further defines an evacuation step and defines the evacuation and coating pressures.

Furthermore, claims 21 - 23 define coated products and the use of an oxygen scavenger.

#### 2. Novelty

US-A-5 837 361 describes a process for coating glass with a multilayer stack comprising oxide layers and a silver layer. According to Example 1 the sputtering of the metallic silver layer takes place in an atmosphere containing hydrogen. since bismuth oxide is one of the layers in the examples, the teaching of US-A-5 837 361 is excluded from claim 1 of the application. US-A-5 837 361 is silent on the evacuation step and pressures defined in claim 19.

Therefore, the processes of claims 1 - 20 are new w.r.t. US-A-5 837 361.

However, claims 21 and 22 define products produced by a process according to one of the process claims ("product-by-process claims").

It is considered that the products obtained according to D1 are not different from the products defined in claims 21 and 22, since the hydrogen as used in D1 acts as an oxygen scavenger, and it is not apparent (e.g. from the present description) that oxygen scavengers different from hydrogen have an effect on the coated product that makes the coated products distinguishable from the ones obtained in D1.

Furthermore, the use of claim 23 does not seem to be new with respect to D1, since the hydrogen as used in D1 acts as an oxygen scavenger in the same process as defined in claim 23, although it is not mentioned in D1 as having this effect.

# INTERNATIONAL PRELIMINARY

International application No. PCT/GB00/00402

## **EXAMINATION REPORT - SEPARATE SHEET**

## Re It m VI

Certain documents cited

Certain published documents (Rule 70.10)

Application No Patent No

Publication date (day/month/year)

Filing date (day/month/year) Priority date (valid claim) (day/month/year)

EP-A-983 973

08.03.2000

02.08.1999

04.08.1998

In this document the use an oxygen scavenger in the sputtering atmosphere is mentioned. Although the oxygen scavenger is only used during the deposition of the metal oxide layer over the silver layer, this interferes with the embodiment of the invention described on page 3, paragraph 6, according to which the oxygen scavenger leaks from second coating atmosphere into the first. The fact that this might happen in state of the art processes (as the one disclosed in EP-A-983 973) is confirmed by GB-A-2 129 831, page 4, lines 60 - 63.

## P NT COOPERATION TREATY

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## INTERNATIONAL SEARCH REPORT

(PCT Article 18 and Rules 43 and 44)

Applicant's or agent's file reference	FOR FURTHER see Notification of Transmittal of International Search Report (Form PCT/ISA/220) as well as, where applicable, item 5 below.									
4576F/JAK International application No.	International filing date (day/month/year)	(Earliest) Priority Date (day/month/year)								
PCT/GB 00/00402	10/02/2000	12/02/1999								
Applicant	10/02/2000	12/02/1999								
PILKINGTON PLC et al.										
This International Search Report has been according to Article 18. A copy is being tra	n prepared by this International Searching Auth Insmitted to the International Bureau.	ority and is transmitted to the applicant								
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This International Search Report consists  It is also accompanied by	of a total of2 sheets. a copy of each prior art document cited in this	report								
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1. Basis of the report		to of the state of								
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2. Certain claims were four	nd unsearchable (See Box I).									
3. Unity of Invention is lace	dng (see Box II).									
4. With regard to the <b>title</b> ,										
The text is approved as sul	bmitted by the applicant.									
the text has been establish	hed by this Authority to read as follows:									
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the text has been established, according to Rule 38.2(b), by this Authority as it appears in Box III. The applicant may, within one month from the date of mailing of this international search report, submit comments to this Authority.										
6. The figure of the drawings to be publi	shed with the abstract is Figure No.									
as suggested by the applic	cant.	X None of the figures.								
because the applicant faile										
because this figure better	characterizes the invention.									

# INTERNATIONAL SEARCH REPORT

International Application No PC 3 00/00402

A. CLASSIFICATION OF SUBJECT MATTER IFG 7 . C03C17/36 C03C C03C17/09 C23C14/54 According to International Patent Classification (IPC) or to both national classification and IPC **B. FIELDS SEARCHED** Minimum documentation searched (classification system followed by classification symbols) IPC 7 CO3C C23C Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched Electronic data base consulted during the international search (name of data base and, where practical, search terms used) C. DOCUMENTS CONSIDERED TO BE RELEVANT Citation of document, with indication, where appropriate, of the relevant passages Relevant to claim No. EP 0 983 973 A (FLACHGLAS AG ; PILKINGTON Ε 1-7, BROTHERS PLC (GB)) 11-18, 8 March 2000 (2000-03-08) 20-23 \*cited in view of the embodiment of the invention described on page 3, par. 6\* the whole document X US 5 837 361 A (HEINZ DECEASED BERNHARD 21-23 ET AL) 17 November 1998 (1998-11-17) cited in the application claims; example 1 1-20 GB 2 129 831 A (PILKINGTON BROTHERS PLC) Α 1-23 23 May 1984 (1984-05-23) cited in the application page 1, line 40 -page 2, line 10 page 4, line 60 - line 63 Further documents are listed in the continuation of box C. Patent family members are listed in annex. Special categories of cited documents: "T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the "A" document defining the general state of the art which is not considered to be of particular relevance earlier document but published on or after the international "X" document of particular relevance; the claimed invention filing date cannot be considered novel or cannot be considered to document which may throw doubts on priority claim(s) or involve an inventive step when the document is taken alone which is cited to establish the publication date of another citation or other special reason (as specified) "Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such docu-ments, such combination being obvious to a person skilled "O" document referring to an oral disclosure, use, exhibition or other means document published prior to the international filing date but later than the priority date claimed "&" document member of the same patent family Date of the actual completion of the international search Date of mailing of the international search report 18 April 2000 27/04/2000 Name and mailing address of the ISA **Authorized officer** European Patent Office, P.B. 5818 Patentlaan 2 NL - 2280 HV Rijswijk Tel. (+31-70) 340-2040, Tx. 31 651 epo nl, Fax: (+31-70) 340-3016 Van Bommel, L

## INTERNATIONAL SEARCH REPORT

form on patent family members

International Application No PO 00/00402

Patent document cited in search report	ì.	Publication date	Patent family member(s)	Publication date
EP 0983973	Α	08-03-2000	NONE	
US 5837361	Α	17-11-1998	DE 19541937 ( EP 0773197 / JP 9174751 /	A 14-05-1997
GB 2129831	A	23-05-1984	AT 31525 AU 554729   AU 1928583   CA 1203197   DK 431483   EP 0104870   FI 833385   JP 5024987   JP 59076534   MX 172033   NO 833335   US 4462883   ZA 8306920	B 28-08-1986 A 12-12-1985 A 15-04-1986 A,B, 22-03-1984 A 04-04-1984 A,B 22-03-1984 B 09-04-1993 A 01-05-1984 B 29-11-1993 A,B, 22-03-1984 A 31-07-1984

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#### INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification 7: (11) International Publicati n Number: WO 00/47530 C03C 17/36, 17/09, C23C 14/54 A1 (43) International Publication Date: 17 August 2000 (17.08.00) (21) International Application Number: PCT/GB00/00402 (81) Designated States: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, EE, 10 February 2000 (10.02.00) ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, (22) International Filing Date: KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, (30) Priority Data: US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, 9903056.1 12 February 1999 (12.02.99) GB LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, (71) Applicant (for all designated States except US): PILKINGTON MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, PLC [GB/GB]; Prescot Road, St. Helens, Merseyside WA10 3TT (GB). GA, GN, GW, ML, MR, NE, SN, TD, TG). (72) Inventor; and **Published** (75) Inventor/Applicant (for US only): SIDDLE, John, Robert [GB/GB]; 25 Knowsley Road, Southport, Merseyside PR9 With international search report. 0HW (GB). (74) Agents: HALLIWELL, Anthony, Charles et al.; Group Intellectual Property Dept., Pilkington European Technical Centre, Pilkington plc, Hall Lane, Lathom, Ormskirk, Lancashire L40 5UF (GB).

## (54) Title: IMPROVEMENTS IN COATING GLASS

#### (57) Abstract

A process for the production of a coated substrate, preferably glass, comprising depositing a reflective metal, especially a silver, layer by a low pressure deposition process performed in a coating atmosphere that contains a gaseous oxygen scavenger. The presence of the gaseous oxygen scavenger alleviates oxidation of the silver layer by any oxygen gas present in the coating atmosphere. The gaseous oxygen scavenger may be a hydrocarbon and is preferably methane. The coating process is preferably sputtering.

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### Improvements in Coating Glass

This invention relates to a process for the production of a coated substrate and, in particular, it relates to a process for the production of a coated substrate comprising depositing a reflective metal layer on to a substrate by a low pressure deposition process.

Substrates coated with a reflective metal layer, typically silver 5 nm to 30 nm thick, may be produced with low emissivity and a high visible light transmission i.e. reflecting a high proportion of infra-red radiation incident upon them but allowing visible radiation to pass through. For optimum light transmission the silver layers are sandwiched between anti-reflection layers usually of metal oxide. The use of such coatings on window glass leads to a reduction in heat loss. Substrates having such coatings are described, for example, in UK patent specification GB 2 129 831.

Coatings having multiple (usually two) silver layers, each silver layer being sandwiched between anti-reflection layers, may also be produced. Coatings with multiple silver layers have both low emissivity, and with appropriate layer thicknesses, a low transmission of solar heat.

Coatings with silver layers are produced by deposition processes in a coating atmosphere at low pressure, especially by sequential deposition of a metal oxide antireflection layer, a silver layer, and a metal oxide anti-reflection layer. The metal oxide layers are usually deposited by reactive sputtering in a coating atmosphere containing oxygen and an inert gas (usually argon). Silver and other reflective metal layers are deposited by sputtering in an inert gas (usually argon). In US patent specification 5,837,361 a process for the production of a coating having layers of bismuth oxide (Bi<sub>2</sub>O<sub>3</sub>), zinc oxide, silver, nichrome, tin oxide and bismuth oxide is described, the metal oxide layers being reactively sputtered in an argon atmosphere containing oxygen and the silver layer being sputtered in an argon atmosphere with the addition of 5% by volume hydrogen.

In commercial production of sputtered coatings, sputtering of each layer usually proceeds in a sputtering chamber that has been initially evacuated to high vacuum (usually of about 10<sup>-6</sup> mbar) and then raised to an operating pressure of around 10<sup>-3</sup> mbar by flowing the gases making up the coating atmosphere into the chamber. The operating pressure is low so that the path length of the coating species sputtered from the target is high enough to reduce scattering and thereby maintain the efficiency of the coating process. Deposition of coatings may be performed in a single chamber having a readily changeable atmosphere or multiple,

serially connected deposition chambers each containing the desired atmosphere. In the multiple chamber case, the substrate is moved sequentially between the chambers, which are separated by gas-tight slit valves to alleviate leakage of the coating atmosphere between chambers. It is particularly important to alleviate leakage of oxygen from the metal oxide deposition chambers to the silver deposition chambers because the reflective metal layer oxidises or degrades if deposited in a coating atmosphere containing oxygen. To reduce

deposition chambers to the silver deposition chambers because the reflective metal layer oxidises or degrades if deposited in a coating atmosphere containing oxygen. To reduce leakage further there are usually additional chambers, positioned between the deposition chambers, which are pumped at high rates so that oxygen in the coating atmospheres used for sputtering metal oxide layers is removed before it can leak into the silver deposition chamber.

The need for high pumping rates in the deposition chambers and in the additional chambers requires expensively high pumping capacity, slows production rates considerably and leakage can still occur. Particular problems arise where the substrate to be coated is curved. In order to accommodate the greater cross-section of curved substrates, high clearance slit valves are required with an increased likelihood of leakage and in consequence a need for even higher pumping rates.

We have discovered that a low pressure deposition process for depositing a reflective metal layer can tolerate the presence of oxygen if a gaseous oxygen scavenger is present in the coating atmosphere.

The present invention accordingly provides a process for the production of a coated substrate comprising depositing a reflective metal layer on to a substrate by a low pressure deposition process performed in a coating atmosphere, characterised in that the coating atmosphere contains a gaseous oxygen scavenger, wherein when the reflective metal layer is deposited as a layer in a multilayer coating which also contains a bismuth oxide layer said gaseous oxygen scavenger is not hydrogen.

In a preferred aspect, the present invention provides a process for the production of a coated substrate, characterised in that the coating atmosphere contains a gaseous oxygen scavenger other than hydrogen.

Oxygen can be present at a level that is too low to conveniently measure but nevertheless is high enough to oxidise or degrade the reflective metal layer. Thus, the coating atmosphere may contain the oxygen scavenger as a preventative measure, even if the deposition process is performed in a coating atmosphere that contains no measurable amount of oxygen.

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Usually, the deposition process is performed in a coating atmosphere that contains oxygen (i.e. that contains a measurable amount of oxygen). The presence of oxygen in the coating atmosphere may arise by leakage from a deposition chamber containing a second coating atmosphere that contains oxygen or from outside (e.g. from the air).

The gaseous oxygen scavenger may be any substance capable of combining chemically with oxygen under the conditions of the low pressure deposition process. Such combination may take place in the gas phase or on the surface of the substrate.

Preferably each molecule of the gaseous oxygen scavenger is capable of combining with more than one atom or more preferably with more than one molecule of oxygen. This is advantageous because then only a small amount of oxygen scavenger need be added to the first coating atmosphere. Adding a large amount of oxygen scavenger to the atmosphere may increase the pressure and therefore reduce the efficiency of deposition. Preferably the gaseous oxygen scavenger has a relatively high vapour pressure at room temperature.

It is advantageous if the gaseous oxygen scavenger is such that the products of its interaction with the surface of the reflective metal layer or of its combination with oxygen are themselves gaseous because the likelihood of solids contamination of the reflective metal layer is thereby reduced. A preferred oxygen scavenger is a hydrocarbon (for example an alkane, alkene, or alkyne), more preferably a C<sub>1</sub> to C<sub>4</sub> hydrocarbon (for example ethane, ethylene, acetylene, propane or butane) and most preferably methane. Oxygen scavengers that are less preferred but may also be suitable include hydrogen carbon monoxide, nitric oxide and organic compounds, for example, methanol, ethanol or formaldehyde.

Preferably, the reflective metal layer is deposited in a coating atmosphere comprising a flowing gaseous mixture and wherein the gaseous oxygen scavenger is introduced into the coating atmosphere by incorporation in the flowing gaseous mixture.

The gaseous oxygen scavenger may also or alternatively be introduced into the coating atmosphere by incorporating it into a second coating atmosphere of e.g. a second deposition chamber so that at least some of it can leak from that second coating atmosphere into the first.

The amount of oxygen scavenger in the coating atmosphere should not be so great as to unacceptably increase the pressure, but should be sufficient to alleviate oxidation or degradation of the reflective metal layer. In practice, if the quality of the reflective metal coating deteriorates during deposition (the deterioration is determined, for example, by an increase in sheet resistance), the amount of oxygen scavenger in the coating atmosphere would be increased to reverse, alleviate or prevent the deterioration.

Thus, preferably, the coating atmosphere contains the gaseous oxygen scavenger in an amount that is sufficient to alleviate oxidation and/or degradation of the reflective metal layer.

Usually the coating atmosphere contains a measurable amount of oxygen and contains the gaseous oxygen scavenger in an amount that exceeds 15 mol% of the amount of oxygen, preferably that exceeds 30 mol% of the amount of oxygen, and more preferably that exceeds 50 mol%, of the amount of oxygen.

Preferably, the reflective metal layer is a silver layer, and preferably the reflective metal layer has a thickness in the range 5 to 30 nm, more preferably in the range 7 to 18 nm. At thicknesses lower than about 5 nm the reflective metal layer may be discontinuous (this results from the growth mechanism of a layer and may occur even on a flat substrate) and will then not possess the properties of the bulk metal resulting in poor infra red reflecting properties. Thicknesses higher than about 30 nm may cause the coated glass to have too high a visible light reflectivity.

It is known to estimate the infra red reflection of reflective metal layers by measuring the sheet resistance of the coating. A high sheet resistance indicates poor infra red reflecting properties (i.e. high emissivity), whereas a low sheet resistance indicates good infra red reflecting properties (i.e. low emissivity). Oxidation or oxygen induced degradation of a reflective metal layer increases the sheet resistance with consequently poorer infra red reflecting properties. The sheet resistance of a layer is defined as:

$$R_s = \rho / d$$

where  $\rho$  is the resistivity of the layer, and d is its physical thickness (see, for example, *Thin Technology*, R.W. Berry, P.M. Hall and M.T. Harris (D. Van Nostrand, 1968) pp 329-331). The units of sheet resistance are  $\Omega$  / square.

In the present invention, preferably the sheet resistance of the reflective metal layer is below  $12 \Omega$  / square. It is advantageous if, in the process, the coating atmosphere contains a measurable amount of oxygen and the sheet resistance of the reflective metal layer deposited in a first coating atmosphere containing oxygen is below  $12 \Omega$ /square, preferably below about  $8 \Omega$ /square.

In a preferred embodiment, the process additionally comprises depositing a metal oxide anti-reflection layer by a low pressure deposition process before depositing the reflective metal layer. The metal oxide layer will usually be deposited from a coating atmosphere that contains oxygen. Usually, at least two metal oxide anti-reflection layers will be deposited so

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that the reflective metal layer is sandwiched between metal oxide anti-reflection layers. When two or more reflective metal layers are deposited (e.g. to provide a coating with low solar heat transmission) each reflective metal layer will usually be sandwiched between metal oxide anti-reflection layers. Examples of metal oxides suitable for use as anti-reflection layers include: zinc oxide, tin oxide, silicon oxide, zirconium oxide, titanium oxide, niobium oxide, molybdenum oxide, tungsten oxide, silicon nitride, silicon oxynitride and silicon oxycarbide. Additional layers of metal oxide, metals (e.g. nichrome, inconel or titanium) or other materials may also be present in the multi-layer coating by, for example, being deposited between the metal oxide anti-reflection layers and the reflective metal layers and/or between the substrate and a metal oxide layer.

Low pressure deposition processes are performed in flowing gas at pressures of below about 10<sup>-1</sup> mbar, or preferably lower and include such processes as sputtering, reactive sputtering, evaporation and other forms of physical vapour deposition. The preferred low pressure deposition process for depositing the reflective metal layer is sputtering.

In prior art processes, deposition of each layer usually proceeds in a sputtering chamber, which has been initially evacuated to about 10<sup>-6</sup> mbar to ensure removal of air, especially oxygen. The pressure of the chamber is then raised to an operating pressure of approximately 10<sup>-3</sup> mbar by injection of the gases making up the coating atmosphere (usually argon for sputtering of the reflective metal and a mixture of argon and oxygen for sputtering of metal oxides).

The present invention is of particular benefit because with a gaseous oxygen scavenger present in the coating atmosphere, the deposition process is better able to tolerate incomplete removal of air.

Thus, in one embodiment, the present invention additionally provides a low pressure process for the deposition of a reflective metal layer on a substrate, performed in a deposition chamber containing a coating atmosphere, comprising evacuating the deposition chamber to a low first pressure, introducing a coating gas into the deposition chamber thereby raising the pressure therein to a higher second pressure of about 10<sup>-3</sup> mbar, and sputtering the reflective metal layer at the second pressure, characterised in that the first pressure is about 10<sup>-4</sup> mbar and in that the coating atmosphere contains a gaseous oxygen scavenger.

This is advantageous because evacuating to a higher pressure is more easily, rapidly and cheaply achieved (particularly because a lower pumping capacity is required).

The substrate to be coated is preferably glass but may be, for example, a transparent plastics substrate. The substrate may be flat or curved.

Coated glass produced by a process according to the invention has uses in many areas of glass use including in multiple glazing units and in laminated glass. Thus, in a further aspect the present invention provides coated glass comprising a glass substrate and a multilayer coating deposited on a surface of the glass substrate, wherein said multilayer coating comprises, in sequence, a first metal oxide anti-reflection layer, a reflective metal layer and a second metal oxide anti-reflection layer, characterised in that the reflective metal layer is deposited by a low pressure deposition process performed in a coating atmosphere containing a gaseous oxygen scavenger other than hydrogen.

In a further embodiment, the present invention provides use of a gaseous oxygen scavenger to reduce oxidation or oxygen induced degradation of a reflective metal layer in a process for the production of a coated substrate, said process comprising depositing the reflective metal layer on to a substrate by a low pressure deposition process performed in a coating atmosphere containing the oxygen scavenger.

The invention is illustrated by the following Examples in which silver reflective metal layers were deposited on glass substrates by sputtering in a coating atmosphere containing argon, oxygen to simulate oxygen leakage and methane as gaseous oxygen scavenger.

#### Examples 1-5

Layers of silver were deposited on soda-lime glass substrates (of dimension 20 x 20 cm, 20 x 10 cm or 20 x 40 cm) at room temperature and at a pressure of 2 x 10<sup>-3</sup> mbar by DC magnetron sputtering using a silver target of 99.9% purity and a power density (over approximately 160 cm<sup>2</sup>) of about 3.1 W/cm<sup>2</sup>. The coating atmosphere consisted of argon, oxygen and methane. All gases were obtained from B.O.C. Ltd and were Zero grade.

The glass substrates were positioned vertically in a holder and advanced at a glass traversal speed of 10-35 cm/min through the sputtering zone with a coating aperture of dimension approximately 1 cm.

After coating, the thickness of the silver layer was measured by computer fitting the optical transmission and reflection spectra of the coated glass, the spectra having been determined using a Hitachi U400 spectrophotometer.

The sheet resistance (in ohm/square) of the silver coatings was determined by a non-contact conductance monitor (Delcon Instruments 717 Conductance monitor).

Table 1 describes, for Examples 1-5, the flow rates of the gases in the coating atmosphere (in standard cm<sup>3</sup> per minute), the glass traversal speed, the thickness of the silver layer as determined and the sheet resistance of the coated glass.

## Comparative Examples A and B

Comparative Example A was conducted under the same conditions as Example 1 except that no oxygen and no methane were present in the coating atmosphere.

Comparative Example B was also conducted under the same conditions as Example 1 except that no methane was present in the coating atmosphere.

Table 2 describes, for Comparative Examples A and B, the flow rates of the gases in the coating atmosphere, (in standard cm<sup>3</sup>/min), the glass traversal speed, the thickness of the silver layer and the sheet resistance of the coated glass.

Table 1

Example	Flow rates of gases (standard cm <sup>3</sup> /min)		Glass traversal speed (cm/min)	Thickness of silver layer (nm)	Sheet resistance (Ω/square)	
<u> </u>	Ar	$O_2$	CH <sub>4</sub>			
1	22	4	6	35	7.3	8.1
2	22	4	6	25	11.6	5.3
3	22	4	0.6	35	9.2	12.0
4	22	40	20	20	8.7	11.9
5	22	40	30	10	15	3.8

Table 2

Comparative Example	Flow rates of gases (standard cm³/min)		Glass traversal speed (cm/min)	Thickness of silver layer (nm)	Sheet resistance (Ω/square)	
	Ar	$O_2$	CH <sub>4</sub>			
Α	22	-	-	35	9.2	5.0
В	22	4	-	35	9.2	12.5

#### Claims

- 1. A process for the production of a coated substrate comprising depositing a reflective metal layer on to a substrate by a low pressure deposition process performed in a coating atmosphere, characterised in that the coating atmosphere contains a gaseous oxygen scavenger, wherein when the reflective metal layer is deposited as a layer in a multilayer coating which also contains a bismuth oxide layer, said gaseous oxygen scavenger is not hydrogen
- 2. A process as claimed in claim 1 wherein the process is characterised in that the coating atmosphere contains a gaseous oxygen scavenger other than hydrogen.
- 3. A process as claimed in claim 1 or claim 2 wherein each molecule of the gaseous oxygen scavenger is capable of combining with more than one atom of oxygen.
- 4. A process as claimed in any one of the preceding claims wherein the gaseous oxygen scavenger is a hydrocarbon.
- 5. A process as claimed in claim 4 wherein the gaseous oxygen scavenger is a  $C_1$  to  $C_4$  hydrocarbon.
- 6. A process as claimed in claim 5 wherein the gaseous oxygen scavenger is methane.
- 7. A process as claimed in any one of the preceding claims wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that is sufficient to alleviate oxidation and/or degradation of the reflective metal layer.
- 8. A process as claimed in one of the preceding claims wherein the coating atmosphere contains a measurable amount of oxygen and contains the gaseous oxygen scavenger in an amount that exceeds 15 mol% of the amount of oxygen.
- 9. A process as claimed in claim 8 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that exceeds 30 mol% of the amount of oxygen.

- 10. A process as claimed in claim 9 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that exceeds 50 mol% of the amount of oxygen.
- 11. A process as claimed in any one of the preceding claims wherein the reflective metal layer is a silver layer.
- 12. A process as claimed in any one of the preceding claims wherein the reflective metal layer has a thickness in the range 5 to 30 nm.
- 13. A process as claimed in claim 12 wherein the reflective metal layer has a thickness in the range 7 to 18 nm.
- 14. A process as claimed in any one of the preceding claims wherein the sheet resistance of the reflective metal layer is below 12  $\Omega$  / square.
- 15. A process as claimed in any one of the preceding claims wherein the coating atmosphere contains a measurable amount of oxygen and the sheet resistance of the reflective metal layer deposited in the coating atmosphere is below  $12 \Omega$  / square.
- 16. A process as claimed in claim 15 wherein the sheet resistance of the reflective metal layer deposited in the coating atmosphere is below 8  $\Omega$  / square.
- 17. A process as claimed in the preceding claims wherein the low pressure deposition process for depositing the reflective metal layer is sputtering.
- 18. A process for production of a coated substrate as claimed in any one of the preceding claims that additionally comprises depositing a metal oxide anti-reflection layer by a low pressure deposition process before depositing the reflective metal layer.
- 19. A low pressure process for the deposition of a reflective metal layer on a substrate, performed in a deposition chamber containing a coating atmosphere, comprising evacuating the deposition chamber to a low first pressure, introducing a coating gas into the deposition chamber thereby raising the pressure therein to a higher second pressure

of about 10<sup>-3</sup> mbar, and sputtering the reflective metal layer at the second pressure, characterised in that the first pressure is about 10<sup>-4</sup> mbar and in that the coating atmosphere contains a gaseous oxygen scavenger.

- 20. A process as claimed in any one of the preceding claims wherein the substrate is curved.
- 21. Coated glass produced by a process as claimed in any one of the preceding claims.
- 22. Coated glass comprising a glass substrate and a multilayer coating deposited on a surface of the glass substrate, wherein said multilayer coating comprises, in sequence, a first metal oxide anti-reflection layer, a reflective metal layer and a second metal oxide anti-reflection layer, characterised in that the reflective metal layer is deposited by a low pressure deposition process performed in a coating atmosphere containing a gaseous oxygen scavenger other than hydrogen.
- 23. Use of a gaseous oxygen scavenger to reduce oxidation or oxygen induced degradation of a reflective metal layer in a process for the production of a coated substrate, said process comprising depositing the reflective metal layer on to a substrate by a low pressure deposition process performed in a coating atmosphere containing the oxygen scavenger.

A. CLASSI IPC 7	FICATION OF SUBJECT MATTER C03C17/36 C03C17/09 C23C14/5	<b>34</b>									
According to international Patent Classification (IPC) or to both national classification and IPC											
B. FIELDS SEARCHED											
Minimum documentation searched (classification system followed by classification symbols)  IPC 7 C03C C23C											
Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched											
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C. DOCUM	ENTS CONSIDERED TO BE RELEVANT										
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Furti	her documents are listed in the continuation of box C.	X Patent family members are lists	ed in annex.								
"A" docume consid "E" earlier of filing of "L" docume which citation "O" docume other in "P" docume	ent defining the general state of the art which is not lered to be of particular relevance document but published on or after the international late ent which may throw doubts on priority claim(e) or is cited to establish the publication date of another in or other special reason (as specified) ent referring to an oral disclosure, use, exhibition or means ent published prior to the international filing date but nan the priority date claimed	or priority date and not in conflict wi cited to understand the principle or invention  "X" document of particular relevance; the cannot be considered novel or cannot be considered novel or cannot have an inventive step when the involve an inventive step when the cannot be considered to involve an document is combined with one or	nent of particular relevance; the claimed invention of be considered novel or cannot be considered to ve an inventive step when the document is taken alone sent of particular relevance; the claimed invention of be considered to involve an inventive step when the ment is combined with one or more other such document, such combination being obvious to a person skilled at.								
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